

(12) International Application Status Report

Received at International Bureau: 10 November 2017 (10.11.2017)

Information valid as of: 28 January 2019 (28.01.2019)

Report generated on: 18 September 2019 (18.09.2019)

(10) Publication number:

WO2019/033578

(43) Publication date:

21 February 2019 (21.02.2019)

(26) Publication language:

Chinese (ZH)

(21) Application Number:

PCT/CN2017/109090

(22) Filing Date:

02 November 2017 (02.11.2017)

(25) Filing language:

Chinese (ZH)

(31) Priority number(s):

201710714005.4 (CN)

(31) Priority date(s):

18 August 2017 (18.08.2017)

(31) Priority status:

Priority document received (in compliance with PCT Rule 17.1)

(51) International Patent Classification:

H01L 51/52 (2006.01); *H01L 51/56* (2006.01)

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(54) Title (EN): FLEXIBLE SUBSTRATE OF FLEXIBLE OLED DISPLAY PANEL AND MANUFACTURING METHOD THEREOF

(54) Title (FR): SUBSTRAT SOUPLE DE PANNEAU D'AFFICHAGE OLED SOUPLE ET SON PROCÉDÉ DE FABRICATION

(54) Title (ZH): 柔性OLED显示面板的柔性基底及其制备方法

(57) Abstract:

(EN): Provided is a manufacturing method of a flexible substrate of an OLED display panel, comprising the following steps: S10, providing a first polyimide layer (201); S20, manufacturing a first silicon oxide layer (202) on a surface of the first polyimide layer (201); S30, manufacturing a second silicon oxide layer (203) on a surface of the first silicon oxide layer (202); S40, manufacturing an amorphous silicon layer (204) on a surface of the second silicon oxide layer (203); and S50, manufacturing a second polyimide layer (205) on a surface of the amorphous silicon layer (204).

(FR): La présente invention concerne un procédé de fabrication d'un substrat souple d'un panneau d'affichage OLED, comprenant les étapes suivantes consistant : S10, à fournir une première couche de polyimide (201) ; S20, à fabriquer une première couche d'oxyde de silicium (202) sur une surface de la première couche de polyimide (201) ; S30, à fabriquer une seconde couche d'oxyde de silicium (203) sur une surface de la première couche d'oxyde de silicium (202) ; S40, à fabriquer une couche de silicium amorphe (204) sur une surface de la seconde couche d'oxyde de silicium (203) ; et S50, à fabriquer une seconde couche de polyimide (205) sur une surface de la couche de silicium amorphe (204).

(ZH): 一种OLED显示面板的柔性基底制备方法,方法包括以下步骤:S10,提供第一聚酰亚胺层(201);S20,在第一聚酰亚胺层(201)表面制备第一氧化硅层(202);S30,在第一氧化硅层(202)表面制备第二氧化硅层(203);S40,在第二氧化硅层(203)表面制备非晶硅层(204);S50,在非晶硅层(204)表面制备第二聚酰亚胺层(205)。

International search report:

International Report on Patentability (IPRP) Chapter II of the PCT:

Not available

(81) Designated States:

AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, JO, JP, KE, KG, KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW

European Patent Office (EPO) : AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR

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